

PTO-1449	Application No. <b>10/623757</b>		Applicant(s) <b>Jin (nmi) Zhao, et al.</b>
	Docket Number TI-35855 (032350.B505)	Group Art Unit <b>Unknown</b>	Filing Date <b>July 21, 2003</b>

## U.S. PATENT DOCUMENTS

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						YES	NO
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L							
M							
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	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
/F.S.	O G. Bruno, et al., "Study of the $NF_3$ plasma cleaning of reactors for amorphous silicon deposition," © 1994 American Vacuum Society, J. Vac. Sci. Technol. A 12(3), pages 690-698.	May/June 1994
/F.S.	P Srihari Ponnekanti, et al., "Failure mechanisms of anodized aluminum parts used in chemical vapor deposition chambers," © 1996 American Vacuum Society, J. Vac. Sci. Technol. A 14(3), pages 1127-1131.	May/June 1996
/F.S.	Q Hsin-Pai Hsueh, et al., "Ion energy distributions and optical emission spectra in $NF_3$ -based process chamber cleaning plasmas," © 2001 American Vacuum Society, J. Vac. Sci. Technol. B 19(4), pages 1346-1357.	Jul/Aug 2001
	R	
EXAMINER /Francis Smith/		DATE CONSIDERED 12/12/2007
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.		

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